

NS6130-10-1465

TUNGSTEN OXIDE

Sputtering Target

Quick Facts

Product	:	Tungsten Oxide Sputtering Target
Stock No	:	NS6130-10-1465
CAS	:	1314-35-8
Molecular Formula	:	WO ₃
Form	:	Solid

Technical Specification

Diameter	Thickness	Purity
50.8 mm ± 1mm	3 mm ± 0.5mm	99.9%

Tungsten oxide (WO₃) sputtering target is a material used in the production of thin films by sputtering. Tungsten oxide has a high sensitivity to these gases, making it an effective material for use in gas sensors. Tungsten oxide thin films are used in the production of solar cells as a photoanode. Tungsten oxide has a high electron mobility, which makes it an ideal material for use in photoanodes. Tungsten oxide thin films are used in the production of electrochromic devices, such as displays and smart mirrors.



* This image is for graphic purposes only and does not represent the actual product.

